



<b>INFORMATION DISCLOSURE CITATION</b>  <b>PTO-1449</b>	<b>Atty. Docket No.</b> NTI-022	<b>Serial No.</b> 10/003,358-4650
	<b>Applicant</b> CHANG, Fang-Cheng	
	<b>Filing Date</b> 11/14/2001	<b>Group</b> 2151 2825

**U.S. PATENT DOCUMENTS**

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
JSA	5,326,659	7/5/1994	Liu, et al.	430	5	3/5/1992
	5,572,598	11/5/1996	Wihl, et al.	382	144	2/25/1994
	5,795,688	8/18/1998	Burdorf, et al.	430	30	8/14/1996
	5,804,340	9/8/1998	Garza, et al.	430	5	12/23/1996
	5,849,440	12/15/1998	Lucase, et al.	430	5	1/29/1997
	6,016,357	1/18/2000	Neary, et al.	382	144	6/16/1997
	6,023,328	2/8/2000	Pierrat	237.4	2/23/1998	
	6,076,465	6/20/2000	Vacca, et al.	101	481	9/19/1997
	6,078,738	6/20/2000	Garza, et al.	395	500.22	5/8/1997
	6,091,845	7/18/2000	Pierrat, et al.	382	144	2/24/1998
	6,272,236	8/7/2001	Pierrat, et al.	382	144	7/18/2000
	6,171,731 B1	1/9/2001	Medvedeva, et al.	430	5	1/20/1999
	6,334,209 B1	12/25/2001	Hashimoto, et al.	716	21	9/2/1999
	2002/0019729 A1	2/14/2002	Chang, et al.	703	6	8/7/1998
JSA	2002/0035461 A1	3/21/2002	Chang, et al.	703	13	7/16/2001

EXAMINER: James SunDate Considered: 7-26-04

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**FOREIGN PATENT DOCUMENTS**

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
<u>JSR</u>	WO 00/36525 A2	6/22/2000	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 97/13370	4/10/1997	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 98/20327	5/14/1998	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 98/45685	10/15/1998	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 99/38002	7/29/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 99/56113	11/4/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 99/59200	11/18/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 99/67626	12/29/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>
<u>JSR</u>	WO 99/14706 A2/A3	3/25/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>

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EXAMINER'S INITIALS	CITATION
<i>JSA</i>	Spence, C., et al., "Detection of 60(degree) Phase Defects on Alternating PSMs", Advanced Micro Devices, KLA-Tencor, DuPont RTC (2 pages).
	Stimiman, J., et al., "Spatial Filter Models to Describe IC Lithographic Behavior". Precim Corporation, Portland, Oregon (10 pages).
	Sugawara, M., et al., "Defect Printability Study of Attenuated Phase-Shifting Masks for Specifying Inspection Sensitivity", Sony Corporation, Kanagawa, Japan (16 pages).
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	Erdmann, A., "Topography Effects and Wave Aberrations in Advanced PSM-Technology", Fraunhofer Institute of Integrated Circuits (11 pages).
	Fiekowsky, P., "The End of Thresholds: Subwavelength Optical Linewidth Measurement Using the Flux-Area Technique", Automated Visual Inspection (6 pages).
<i>JSA</i>	Neureuther, A., et al., "Modeling Defect-Feature Interactions in the Presence of Aberrations", University of California Berkeley (10 pages).

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*James Sun Lin*

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<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>			
<b>EXAMINER'S INITIALS</b>	<b>CITATION</b>		
<i>JFA</i>	Mathur, B.P., et al., "Quantitative Evaluation of Shape of Image on Photoresist of Square Apertures", IEEE, Transactions On Electron Devices, Vol. 35, No. 3, pp. 294-297, March 1988.		
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	Rieger, M., et al., "System for Lithography Proximity Compensation", Precim Company, Portland, Oregon, September 1993 (28 pages).		
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<i>JFA</i>	Karklin, L., "A Comprehensive Simulation Study of the Photomask Defects Printability", SPIE, Vol. 2621, pp. 490-504 (1995).		

EXAMINER: *Jana J. Smith*

Date Considered:

7-26-04

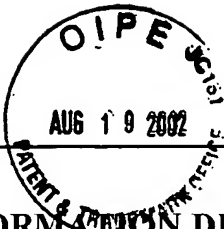
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<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>			
<b>EXAMINER'S INITIALS</b>	<b>CITATION</b>		
<i>JSL</i>	Wiley, J., et al., "The Effect of Off-Axis Illumination on the Printability of Opaque and Transparent Reticle Defects", SPIE, Vol. 2512, pp. 432-440 (1995).		
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<i>JSR</i>	Balasinski, A., et al., "Comparison of Mask Writing Tools and Mask Simulations for 0.16um Devices", IEEE, SEMI Advanced Semiconductor Manufacturing Conference, pp. 372-377 (1999).
<i>JSR</i>	Fiekowsky, P., et al., "Defect Printability Measurement on the KLA-351: Correlation to Defect Sizing Using the AVI Metrology System", SPIE 19th Annual BACUS Symposium on Photomask Technology and Management Conference, pp. 1-6, September 1999.
<i>JSR</i>	Tejnil, E., et al., "Option for At-Wavelength Inspection of Patterned Extreme Ultraviolet Lithography Masks", SPIE Bacus '99, pp. 1-12 (1999).
<i>JSR</i>	Hemar, S., et al., "Finding Killer CD Variations by Full-Reticle CD Mapping", Microlithography World, pp. 4, 6, 8 & 10 (Summer 2000).

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